Lithography

Exposure Tool

ASML PAS 5500/200 i-line 5x Stepper

- 0.35um capable - 150mm wafers

GCA g-line 5x Stepper

- ~1.0um capable - 100mm wafers

Heidelberg DWL 66+

- ~ 0.8um features with 4mm head
- ~ 4.0um features with 20mm head

Karl Suss MA150 1x Contact Aligner

- ~2um capable - 150 mm wafers - i-line filtering for better resolution

Karl Suss MA56 1x Contact Aligner

- ~2um capable - multiple size substrates

Coat / Develop Tools

SVG 88 Coat/Develop Track #1

- Set up for 150mm wafers - MiR 701 resist dispense

SVG 88 Coat/Develop Track #2

- Set up for 150mm wafers - MiR 701 resist dispense

Manual Coat / Develop Tools

CEE Manual Spin Coater

- Use for manual coating of positive photoresists

CEE Manual Spin Coating Station

- Use for manual HDMS prime / coating of positive photoresists

SCS Manual Spin Coater

- Use for manual coating of photoresists, SU8, Polyimides, & Spin on Glass

CEE Manual Developer

- Use for manual spray development of positive photoresists